Investor Relations | 2020 May



Caution

This information contains estimated numbers based on 1st Quarter FY2020 Financial Results comply with the regulations of K-IFRS.

For investors' convenience, it may differ from the Auidit and numbers could be changed in the future.

Estimates are not qualified by external audits. It may changed effected by future business circumstances. For this reason, future financial results may differed from the estimates.

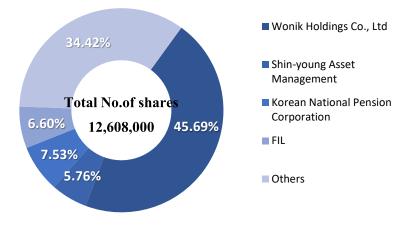
Please note that Wonik Materials and our board members are not responsible for any loss from using this information.

Corporate Status

Corporate Name	Wonik Materials Co., Ltd			
CEO	Han Woo Sung	Yangchung(HQ)	Ochang	
Foundation Date	2006. 12. 04			
Shares Outstanding	12,608,000 (2020.03.31)	OWIGHE AND		
Capital	KRW 6.30 Billion (2020.03.31)			
Employees	415 (2020.03.31)			
Industry	High-purity Speical Gas			
Yangchung(HQ)	 30, Yangcheong 3-gil, Ochang-eup, Cheongwon-gu, Cheongju-si, Chungcheongbuk-do Land 50,845m² / Buildings 13,284m² 	Jeonui	Pangyo	
Yangchung2	 26, Yangcheong 3-gil, Ochang-eup, Cheongwon-gu, Cheongju-si, Chungcheongbuk-do Land 68,970m² / Buildings 3,182m² 			
Ochang	 112, Gwahaksaneop 3-ro, Ochang-eup, Cheongwon-gu, Cheongju-si, Chungcheongbuk-do Land 20,837 m²/Buildings 9,356 m² 			
Jeonui	21-125, Sandan-gil, Jeonui-myeon, Sejong-si – Land 42,160m² /Buildings 6,957m²			
Website	www.wimco.co.kr	-		

Equity Information





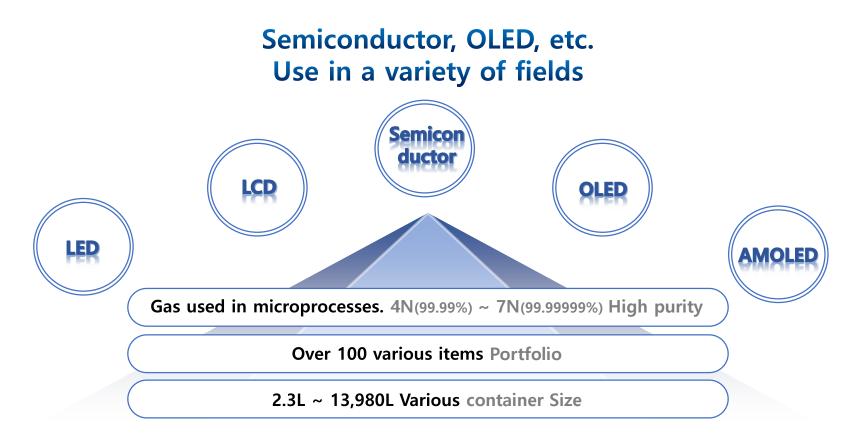
America

WMNA(Nova-kem) Epuity 100%

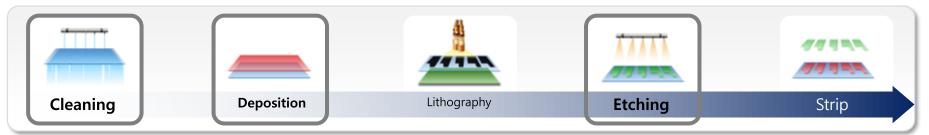
China

XIAN NEW WONIK SEMINCONDUCTOR MATERIALS Co,. Ltd Equity 100% WEINAN NEW WONIK SEMINCONDUCTOR MATERIALS Co,. Ltd Equity 100% XIAN YANG SEMICONDUCTOR TRADE Co., Ltd Equity 100%

Shareholder	No.	Ownership	Remarks	
Wonik Holdings Co., Ltd	5,760,000	45.69%	Major Shareholder	
Korean National Pension Corporation	949,825	7.53%		
FIL	831,817	6.60%		
Shin-yong Asset Management	725,982	5.76%		
Others	4,340,376	34.42%		
Total	12,608,000	100.00%		



Major areas of special gas



Major item

Manufactured Product

Product

Cleaning

F2 MIX

 \cdot The Adoption Rate of Dry Cleaning Process increase with the scale-down of the device

CO2(Low-purity)

• Used in both Wafer Cleaning and Photo Immersion Process for the purpose of improving manufacturing process with the scale-down of the device.

Deposition

N20

Used in deposition of SiO2 by combining it with SiH4 in Semiconductor and LCD manufacturing process.

NH3

Used in deposition of Si3N4(Dielectric Layer) by combining it with SiH4 in Semiconductor and LCD manufacturing process. Combined with TMGa in LED manufacturing process.

Etching

C4F8

Gas used in the etching process of Oxidation Layer (SiO2)

Xe

Gas used for high selectivity in the etching process.

Si2H6

Due to the scale-down of the device, Si2H6 is a process gas that shows superior performance which can't be implemented with SiH4 in the deposition of Silicon.

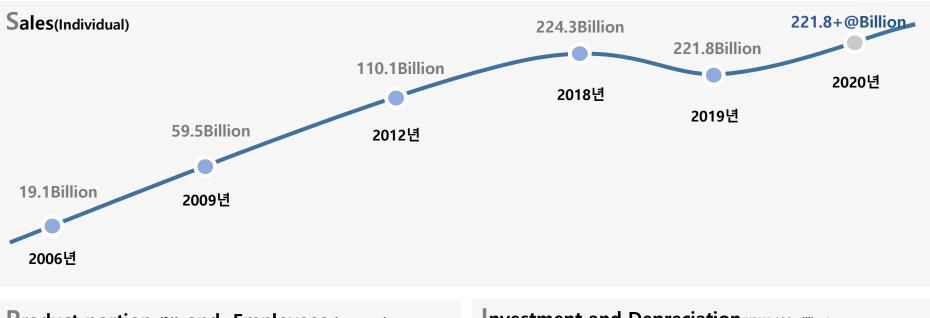
GeH4 MIX

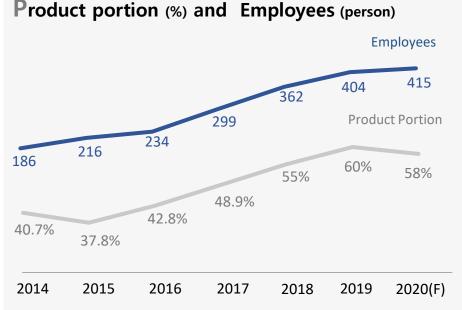
GeH4 Mix is a gas that is combined with SiH4 and deposited in SiGe form.

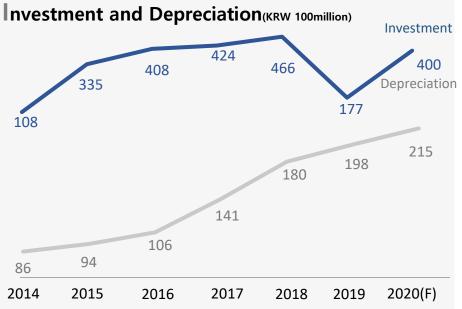
CH2F2

Gas which is used in Etching Process of Nitration Layer (Si3N4)

History







FY2020 1st Quarter Results

2020 1st Quarter Results(Consolidated)

(Unit : KRW1,000,000, %)

2020 1Q							
	2020.1Q	2019.4Q	QOQ	Q O Q (%)	2019.1Q	YOY	YOY (%)
Sales	66,305	58,560	+7,745	+13.2%	51,714	+14,591	+28.2%
Operating Profit	10,820	7,800	+3,020	+38.7%	7,024	+3,796	+54.0%
(%)	16.3%	13.3%	-	-	13.6%	-	-

* K-IFRS Applied

2020 1st Quarter Results(Individual)

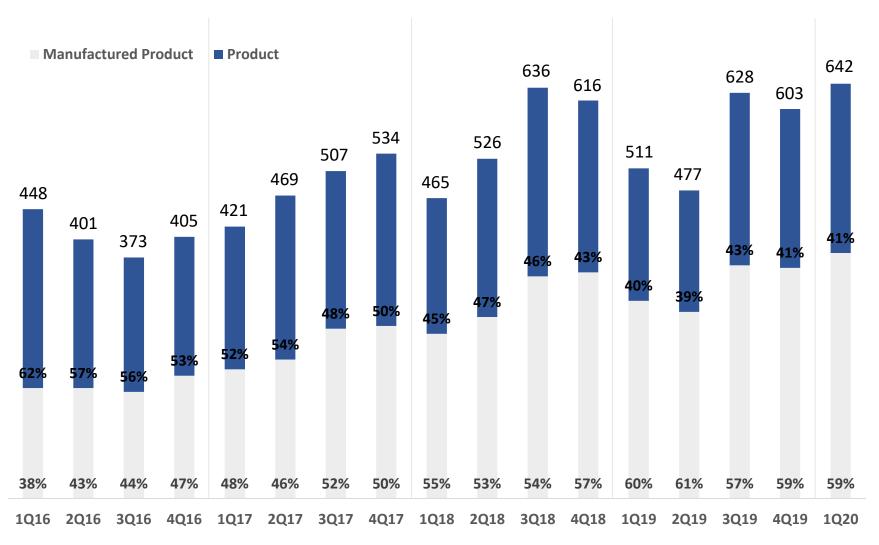
(Unit : KRW1,000,000, %)

2020 1Q							
	2020.1Q	2019.4Q	QOQ	Q O Q (%)	2019.1Q	YOY	YOY (%)
Sales	64,220	60,326	+3,894	+6.5%	51,076	+13,144	+25.7%
Operating Profit	11,494	10,614	+880	+8.3%	7,947	+3,547	+44.6%
(%)	17.9%	17.6%	-	-	15.6%	-	-
EBITDA	16,406	15,584	+822	+5.3%	12,851	+3,555	+27.7%
(%)	25.5%	19.2%	-	-	25.2%	-	-
Net Income	9,568	4,682	+4,886	+104.4%	6,752	+2,816	+41.7%
(%)	14.9%	7.8%	-	-	13.2%	-	-

* K-IFRS Applied

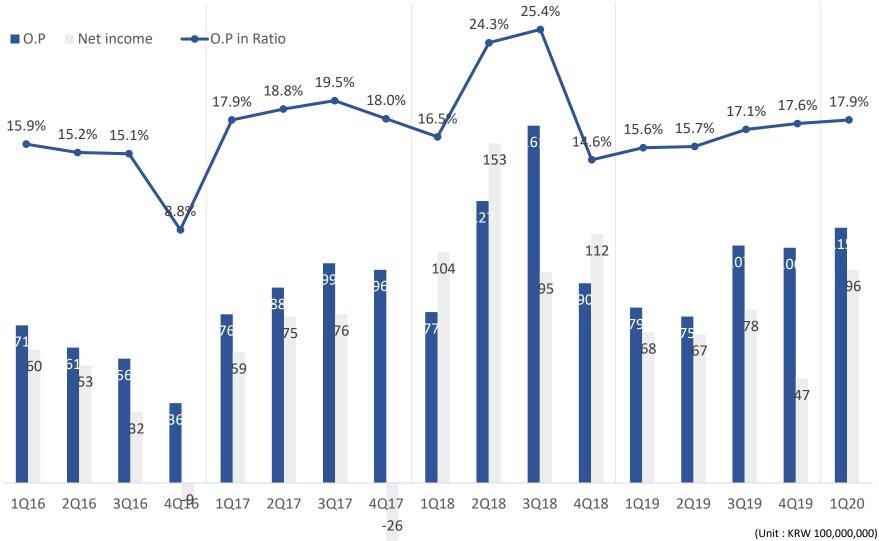
Financial Performance

Sales(Individual)



Financial Results

Operating Profit(Individual)



(Unit : KRW 100,000,000)







